

# Resource Summary Report

Generated by [kravitz2](#) on Jul 29, 2026

## Oxford: PlasmaPro 100 PECVD Plasma Technology

RRID:SCR\_020374

Type: Tool

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### Proper Citation

Oxford: PlasmaPro 100 PECVD Plasma Technology (RRID:SCR\_020374)

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### Resource Information

**URL:** <https://plasma.oxinst.com/products/pecvd/plasmapro-100-pecvd>

**Proper Citation:** Oxford: PlasmaPro 100 PECVD Plasma Technology (RRID:SCR\_020374)

**Description:** PECVD process modules are designed to produce uniformity and high rate films, with control of film properties such as refractive index, stress, electrical characteristics and wet chemical etch rate.

**Resource Type:** instrument resource

**Keywords:** Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

**Availability:** Commercially available

**Resource Name:** Oxford: PlasmaPro 100 PECVD Plasma Technology

**Resource ID:** SCR\_020374

**Alternate IDs:** Model\_Number\_100\_PECVD

**Record Creation Time:** 20220129T080350+0000

**Record Last Update:** 20260725T190926+0000

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### Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 100 PECVD Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 100 PECVD Plasma Technology.

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### Data and Source Information

**Source:** [SciCrunch Registry](#)

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## Usage and Citation Metrics

We have not found any literature mentions for this resource.